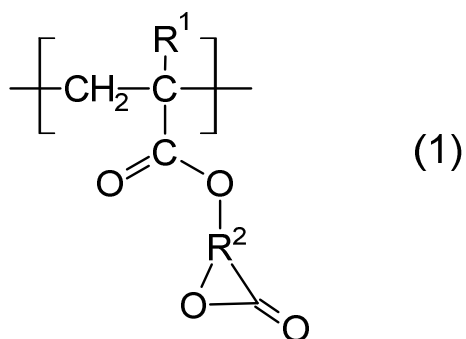


COMPOSITION FOR FORMING RESIST UNDERLAYER FILM

ABSTRACT

There is provided a composition for forming a resist underlayer film containing a polymer having a repeating unit (1) represented by Formula (1) below and a repeating unit (2) other than the repeating unit (1), and a solvent, in which an average particle size of the polymer in a polymer solution containing the polymer is 50 nm or less.



(In Formula (1), R¹ represents a hydrogen atom, a methyl group, or a halogen atom, and R² represents a trivalent hydrocarbon group having 3 to 6 carbon atoms. Here, the lactone structure containing R² is a 5-membered ring or a 6-membered ring.)

[Fig.2A]